

Multi-functional self-cleaning thermochromic films by atmospheric pressure chemical vapour deposition

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Abstract

Thin films of titanium dioxide and vanadium dioxide were deposited onto glass using atmospheric pressure chemical vapour deposition (APCVD). The films were investigated as individual layers and as part of multilayer systems to assess their potential to be combined to offer dual functionality, self-cleaning thermochromic films. The multilayer systems were achieved by deposition of vanadium dioxide with subsequent titanium dioxide deposition and vice-versa. XRD revealed that the titanium dioxide existed exclusively in the anatase form and the vanadium oxide either monoclinic VO₂ or mixed vanadium oxides, depending on the position within the multilayer structure. XPS analysis indicated good stoichiometry in the films, and also suggested that the films remained elementally discrete when deposited in the multilayer systems. The multilayered films were active in the destruction of stearic acid layers under UV radiation and showed good thermochromic switching properties.

Furthermore, the titania over-layer imparted a significant degree of enhanced durability to the underlying thermochromic film. This combination of enhanced durability and ‘self-cleaning’ property, offers interesting potential for wider potential use of this technology.

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1. Introduction

Added value coatings for glass are of significant commercial and scientific interest, particularly so when grown by atmospheric CVD processes, which have advantages in terms of relatively facile translation into production. The ‘self-cleaning’ ability of titania arising from its photocatalytic and hydrophilic nature has been the subject of much previous research. Applications have included self-clean glazing products [1], air (and water) purification [2] and antibacterial systems [3].

The thermochromic behaviour [4] of vanadium dioxide, which can give rise to substantial changes in optical IR transmission, arises via the transition from monoclinic to tetragonal rutile structure. Such effects have been explored for solar control glazing applications. Other potential uses of this temperature-induced phenomenon of the semiconductor-to-metal transition

for vanadium oxides are lithium-ion batteries and the window in solar cells and gas detectors [5].

Vanadium oxides have been grown by a range of techniques including sol–gel technique [6], vacuum evaporation [7], low pressure [8] as well as atmospheric pressure chemical vapour deposition [9,10].

Known issues with vanadium dioxide include its lack of mechanical robustness and moderate chemical durability. In this paper we explore the use of an over-layer of titania, designed to overcome these limitations. Furthermore, the combination of titania and vanadium oxides gives rise to a multi-functional film demonstrating both the thermochromicity of vanadium dioxide and the high photoactivity of titania, which also imparts a “self-cleaning” surface functionality. We report on the growth and the characterisation of these dual functionality films, all of which were produced in an atmospheric pressure chemical vapour deposition (APCVD) reactor. Through the characterisation we show that the multilayers formed have excellent photoactivity and high optical switching properties. Also, we report on the enhanced chemical durability and regeneration of these films, which when combined with the ‘self-cleaning’ property, offers interesting potential for wider potential use of this technology.

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This work represents the first report of both thermochromic and self-clean functional discrete layers within a single multilayered system.

2. Experimental

2.1. Growth

All films were grown on pre-coated (CVD) silica coated barrier glass substrates. The barrier was a (60 nm), amorphous film of SiO₂ designed to prevent diffusion of impurity ions within the float glass (to prevent a reduction in the quality and photoactivity of subsequently deposited film layers). All TiO₂ films were grown using an atmospheric pressure CVD coater described previously [11]. The precursor for titania growth was titanium tetraisopropoxide (7.79×10^{-4} mol min⁻¹) (Aldrich) while the substrate temperature for growth was set to 500 °C. For the vanadium oxides the precursors were vanadium tetrachloride (1.46×10^{-3} mol min⁻¹) (Aldrich) and water (2.3×10^{-6} mol min⁻¹) while the substrate temperature was set to 450 °C. Precursors were transported through the reactor in a nitrogen carrier gas stream.

2.2. Characterisation

Standard techniques of X-ray diffraction (Siemens D5000), uv/visible spectroscopy (Hewlett Packard HP895A) and SEM (Philips XL30) were used to characterise the samples. The morphology of the samples was also assessed by atomic force microscopy (NanoScope IIIa, Digital Inst. Ltd). X-ray photoelectron Spectroscopy, XPS (Kratos AXIS Ultra) with an Al (monochromated) K α radiation source was used to check the surface composition and stoichiometry of the films. It was necessary to use a charge neutraliser as all the samples were insulating, due mainly to the deposition on glass. This tends to shift the peak positions up to 2 eV so the measurements are referenced to the residual C 1s signal at 285 eV. Curve fitting used CASA XP software using a mixture of Gaussian–Lorentzian functions to deconvolute spectra. Rutherford backscattering was also used to assess the bulk stoichiometry and layer thickness (within the multilayer samples) using an analyzing beam of 2 MeV He⁺ with the sample being analysed at normal incidence with a scattering angle of 168° in IBM geometry. Bulk densities for VO₂ of 4.34 g/cm³ and TiO₂ of 4.23 g/cm³ were used for the modelling.

The comparative chemical resistance of the samples was tested by soaking the samples in 2 M sodium hydroxide solution and using an optical microscope to assess the changes.

Photocatalytic behaviour was measured under UV radiation (365 nm) and visible radiation by use of a high intensity lamp (300 W) with a 400 nm cut-off filter. The degradation of stearic acid was followed by FTIR (Bruker, Vector 22). Stearic acid (100 μ l of 10 mmol in methanol) was spun-coated onto the sample. After drying in an oven at 55 °C the sample was exposed to UV light with an intensity of 3 mW cm⁻². The activity of the film was defined in cm⁻¹ min⁻¹, which indicated the rate of reduction in selected stearic acid peaks in the IR region.

The technique used [12] was developed from work described previously [13–15].

The optical properties of the films were measured on a nkd8000 spectrophotometer (Aquila Instruments Ltd) with an incorporated heating stage. Samples were heated from room temperature to 75 °C in 5 °C intervals, in order to observe and assess the thermochromic transition. A wavelength range from 800 to 1700 nm was used with s-polarised incident light at an angle of 30°.

3. Results and discussion

Using atmospheric pressure CVD, multilayers of TiO₂ with an underlayer of VO₂ (TiO₂ on VO₂ on SiO₂-coated glass) and the inverse (VO₂ on TiO₂ on SiO₂-coated glass) were grown. As references, single layers of TiO₂ and VO₂ on glass were also grown under identical conditions, comparable in thickness to the multilayer composites.

3.1. Visual

All films were transparent with less than 2% haze. In the case of the reference TiO₂, the haze was less than 0.5%. Those films containing the vanadium oxides had a greenish tinge, while the reference titania sample was brown due to interference colouration.

3.2. X-ray diffraction

The reference samples of titanium dioxide and vanadium dioxide showed polycrystalline peaks for anatase (JCPDS 21 1272) and monoclinic vanadium dioxide (JCPDS 44 0253), respectively (Fig. 1). X-ray diffraction for the vanadium oxide also showed small signals at 25.3° and 14.6°, which have been assigned to tetragonal V₂O₅ (JCPDS 45 1074). Assignment of all the XRD features can be complex since anatase, rutile and the many forms of vanadium oxides have a number of peaks in similar positions.

Growth of TiO₂ on a VO₂ layer (grown as the reference) established that the TiO₂ was anatase, with monoclinic VO₂ as the underlayer. This suggests that no change occurs within the

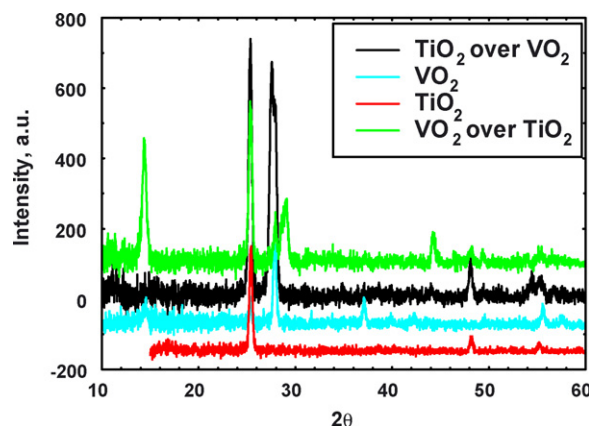


Fig. 1. XRD of multilayer samples and corresponding references.

VO₂ on heating to 500 °C during the deposition of TiO₂. This is not very surprising as the temperature is not much higher than that used to grow the VO₂. However, it is interesting that at this temperature the VO₂ would be expected to be in a tetragonal rutile form and perhaps have a structure-directing influence on the TiO₂ formation with the production of rutile. This does not occur and only anatase is deposited, as established by XRD. This is perhaps still more surprising since Carotta et al. have shown that although for a quite different growth process (sol–gel), that addition of V ions aids the transformation of anatase to rutile on annealing [16].

XRD analysis of the multilayer of TiO₂ capped with an over-layer of VO₂ confirmed the TiO₂ was anatase, with the over-layer containing mainly V₂O₅ (JCPDS 45 1074) although the XRD data contained some contributions from monoclinic VO₂ (27.9° and 55°) and also possibly some orthorhombic V₂O₅ (JCPDS 41 1426) at 44.2° and 49.5°.

The presence of a mixture of vanadium oxides meant that an unambiguous assignment of the XRD data was difficult due to the lack of sufficient numbers of peaks required for accurate indexing.

Since for the two layer structures essentially identical growth conditions were employed, the differences in the nature of the VO₂ films formed in each case can be attributed to the influence of the morphology of the underlying layer—in one case amorphous SiO₂ and in the other TiO₂ in the anatase form. In

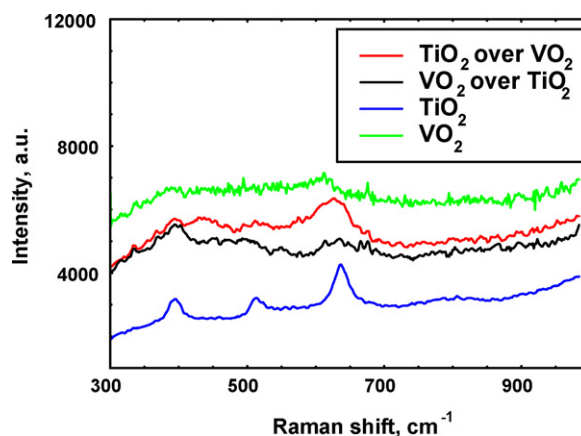


Fig. 2. Raman of the multilayer samples and their references.

this respect, it is noteworthy that there is a 3.6% lattice mismatch between TiO₂ and VO₂ and thus growth of VO₂ on TiO₂ may lead to a highly strained system. This may account for the mixture of vanadium oxides found for these samples.

3.3. Raman spectroscopy

Raman excitation at 514 nm was used to confirm the type of TiO₂ present. To study the vanadium oxides longer wavelength

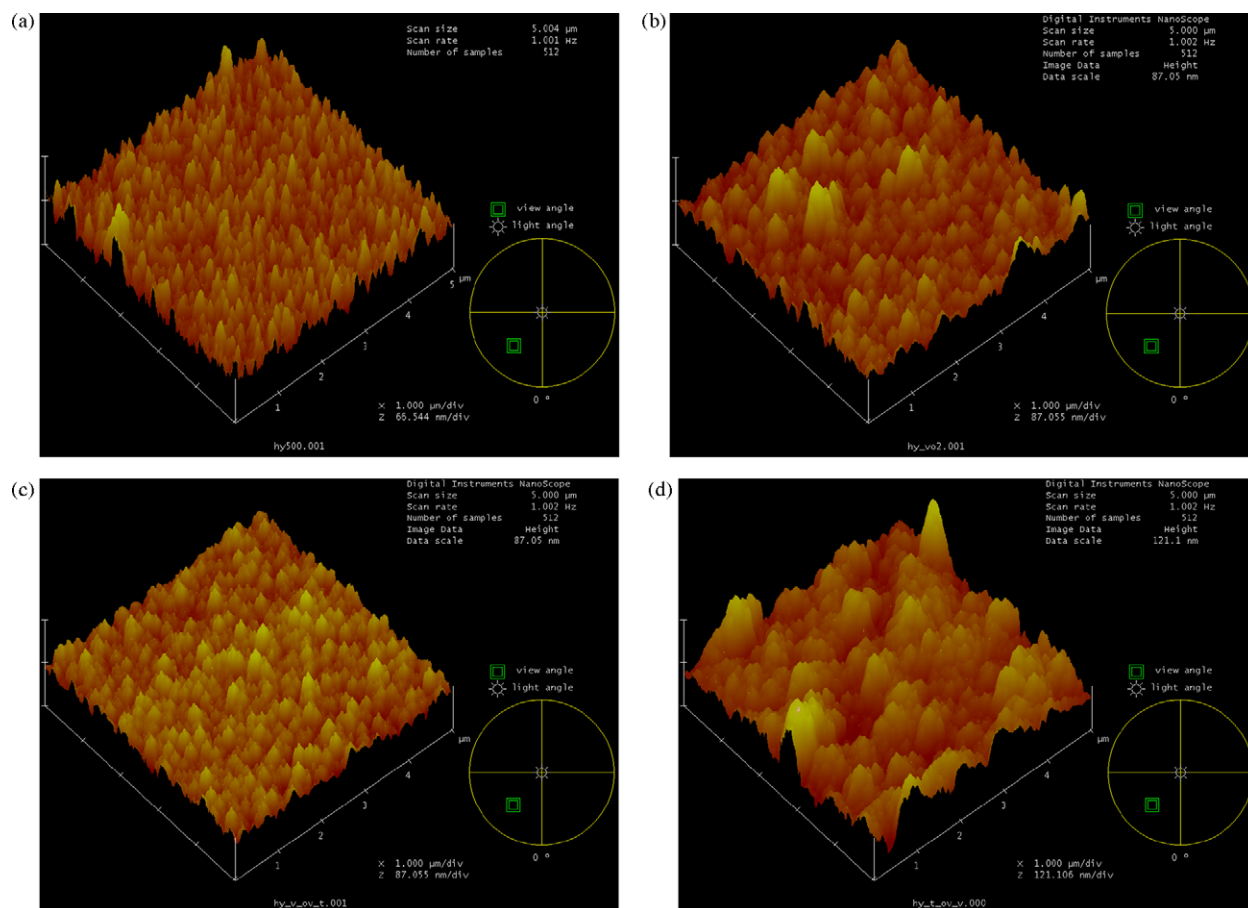


Fig. 3. AFM images, (a) TiO₂, (b) VO₂, (c) VO₂ over TiO₂ and (d) TiO₂ over VO₂.

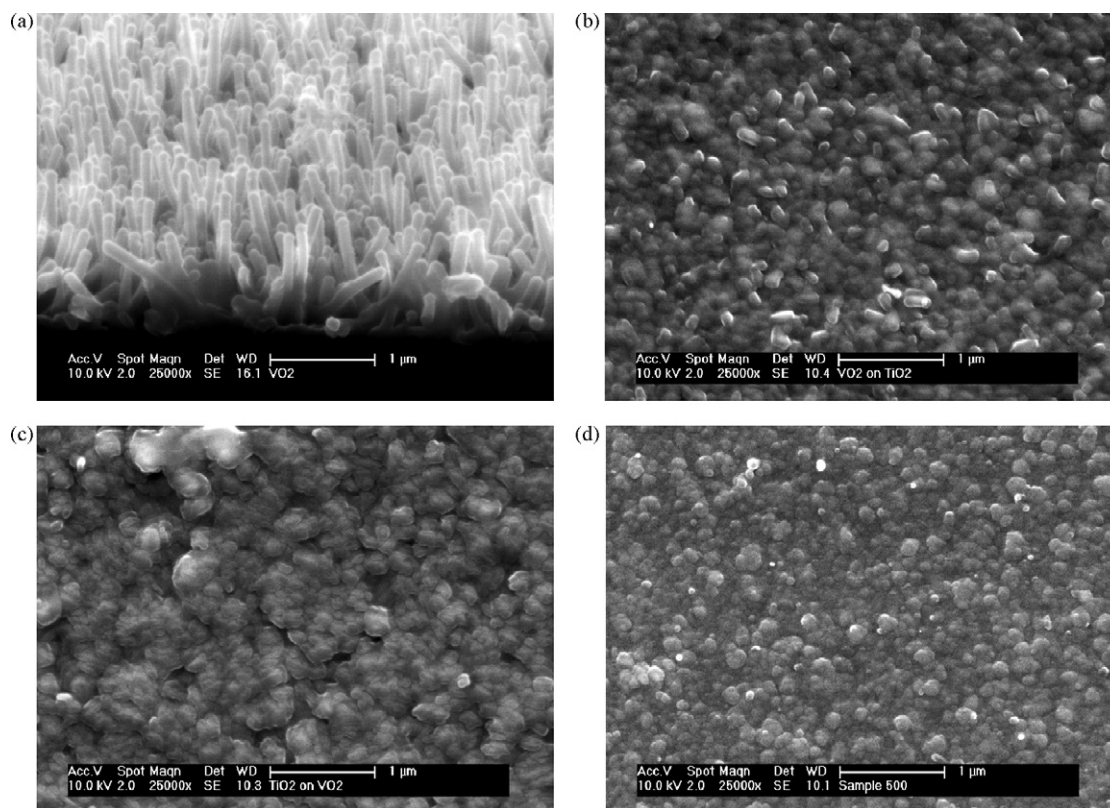


Fig. 4. SEM images of (a) VO₂, (b) VO₂ over TiO₂, (c) TiO₂ over VO₂ and (d) TiO₂.

excitation would be necessary in order to avoid direct absorption of the laser line via the coloured vanadium oxide films. Unfortunately longer wavelength excitation was not available. Raman confirmed that the main form of TiO₂ was anatase (397, 515 and 636 cm⁻¹), although for the sample of TiO₂ grown on VO₂ Fig. 2 reveals that there may be a very small amount of rutile (not detected by XRD), giving rise to the broad peak at 438 cm⁻¹ and the possible shoulder at 604 cm⁻¹.

3.4. Morphology

AFM of the various samples (Fig. 3) established that there was comparatively little difference in morphology and roughness of the reference VO₂ and the multilayer of VO₂ over TiO₂, at both the 5 μm × 5 μm and the 1 μm × 1 μm scale. That of the VO₂ reference having slightly less uniformity over the scale studied. In contrast, this was not the case for the reference TiO₂ sample and the multilayer of TiO₂ over VO₂. The morphology of the TiO₂ reference sample was similar in uniformity and level of roughness to the previous samples, while that of the multilayer (with a TiO₂ over-layer) was much less uniform. In Fig. 3(c and d) a comparison of the multilayers is shown. As can be seen the TiO₂ over VO₂ sample is less uniform in overall structure with a Ra value (21.2 nm, taken from the 5 × 5 plot) at least double that of the VO₂ (10.3 nm), TiO₂ (7.95 nm) or VO₂ on TiO₂ (7.8 nm) samples.

The increased roughness of the multilayer of VO₂ with an over-layer of TiO₂, Fig. 3(d), possibly relates to increased lattice

strain as previously mentioned. However, when VO₂ is grown on TiO₂, Fig. 3(c), the VO₂ coating appears to adopt the texture and contours of the underlying TiO₂ film. Given that the lattice strain argument should apply in both cases, this result suggests that the growth of the VO₂ is more strongly influenced by the morphology of the TiO₂ under layer, to the extent that the under layer acts as a template for growth, which locks in a particular feature size at the expense of the formation of monoclinic VO₂. This argument would be consistent with the XRD data for these samples, which showed that they contained a mixture of vanadium oxides.

SEM of the samples gave a more general view of the morphology, confirming the uniformity of the surface over a wider area. As can be seen in Fig. 4(a) the reference VO₂ sample showed a rod like structure, generally aligned perpendicular to the substrate. These rods were about 108 nm in diameter, with some reaching 800 nm in length. Similar VO₂ rod like structures were seen by Manning and Parkin [17] and also by Qureshi et al. [18] in composite TiO₂-VO₂ films, although in the latter paper their rods were thicker, relating probably to the higher growth temperature used.

However, for growth of VO₂ on top of TiO₂, the surface became more compact, with uniform granular particle morphology (Fig. 4(b)). This structure is similar to that seen by both Sahana et al. [19] and Vernardou et al. [9] for VO₂ grown using vanadyl acetylacetonate rather than vanadium tetrachloride. Growth of TiO₂ over VO₂ (Fig. 4(c)) led to a structure characteristic of anatase growth directly on glass (Fig. 4(d)).

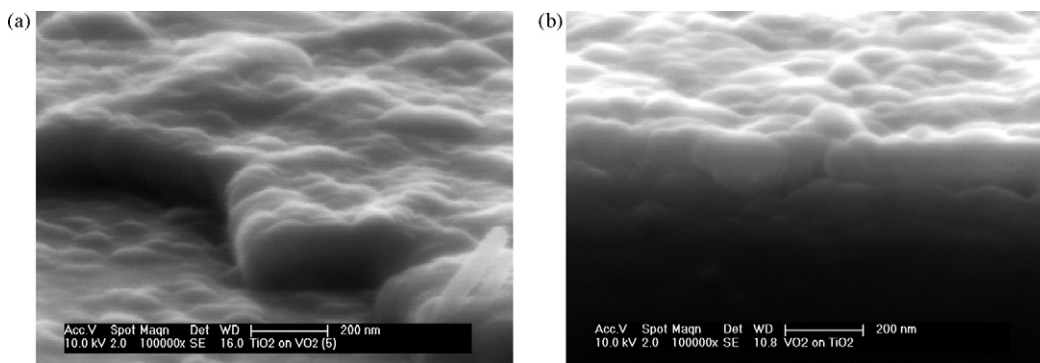


Fig. 5. SEM cross-sectional images of (a) TiO₂ over VO₂ and (b) VO₂ over TiO₂.

Comparison of both multilayers suggested that that of the TiO₂ over VO₂ sample was slightly rougher, although finer detail of the AFM was required to confirm this.

The individual layer thicknesses were assessed using cross-sections (Fig. 5), but it was difficult, particularly for TiO₂ over VO₂, to distinguish the individual components within the multilayers. The smoother transition from VO₂ to TiO₂ (than the inverse growth) suggested that the TiO₂ locked into the underlying structure, taking up the lattice mismatch by internal strain rather than reduction by dislocations and structure changes (as confirmed by XRD), which occurred for TiO₂ over VO₂.

The deposition thickness, established by SEM, was 158 nm for TiO₂ over VO₂ and 198 nm for VO₂ over TiO₂. That for VO₂ over TiO₂ could be split into 112 nm for VO₂ and 86 nm for TiO₂. The samples were grown under identical conditions so the difference in thickness was probably due to growth rate changes caused by the different underlying layers.

3.5. Rutherford backscattering spectroscopy

To identify the thickness of the individual composite of the TiO₂ over VO₂ sample and confirm the bulk compositions and other thickness values it was necessary to use RBS. By fitting the experimental data it is possible to obtain the bulk stoichiometry, although not the oxidation states. By further modelling of the data either the thickness or density can be obtained, as these two parameters are dependent on each other. Fig. 6 shows examples of the RBS measurements, with the points being the experimen-

tal data and the line the modelled fit. Sharp cut-offs (beginning and ends) relating to Ti and V can be seen, as they are distinct layers within the sample. However, the O is seen as a rising edge as it is present in both layers and the substrate. Also present are signals relating to the SiO₂ glass substrate and its impurities (Na and Ca). There is no sign of any carbon contamination in the bulk sample.

In Fig. 6(a) for VO₂ over TiO₂ the RBS shows 2 distinct peaks for V and Ti, while in Fig. 6(b) for TiO₂ over VO₂ only one peak for Ti and V is seen. The element with the greater mass will be at a higher channel number, so for a material with both Ti and V on the surface V would start at 295 and Ti at 287. However, for a multilayer the position of the lower element becomes shifted to lower channel numbers, which would lead to a separation of the signals for VO₂ over TiO₂ (Ti shifting to lower channel numbers) and an amalgamation of the signals for TiO₂ over VO₂.

For all three samples analysed (VO₂, TiO₂ over VO₂ and VO₂ over TiO₂) they were all confirmed to be stoichiometric V₁O₂ and Ti₁O₂. This is in agreement with the X-ray diffraction results for VO₂ and TiO₂ over VO₂. However, the X-ray diffraction result for the vanadium oxide sample over TiO₂ concludes that the upper layer consists of mainly V₂O₅ with a little VO₂. Attempts to fit the RBS data to obtain an increase in the amount of oxygen were not successful. To explain this apparent contradiction it is necessary to consider the possibility that the V₂O₅ is mainly a surface layer with VO₂ underneath. In this case glancing angle X-ray diffraction would give a greater weighting

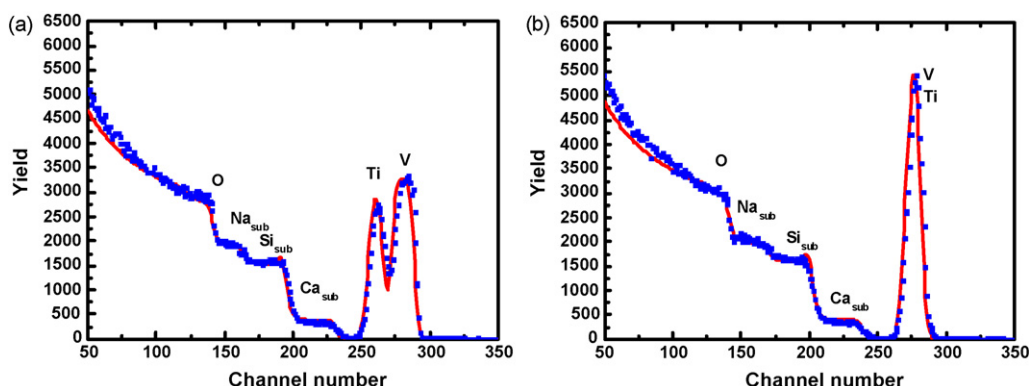


Fig. 6. RBS measurements for (a) VO₂ over TiO₂ and (b) TiO₂ over VO₂.

to the surface. A secondary confirmation of the presence of a reasonable amount of VO₂ is shown later in the thermochromic measurements. If no or negligible VO₂ was present there would not have been a well defined thermochromic change round 55 °C.

The component layers for VO₂ over TiO₂ were calculated to be 100 nm and 70 nm, respectively. These values are in agreement with those obtained from the SEM for VO₂ and TiO₂ layers of 112 ± 11 nm and 86 ± 12 nm, respectively. The TiO₂ over VO₂ sample gave 70 nm for VO₂ and 55 nm for the TiO₂ layer. The total sample thickness of 125 nm is lower than that from the SEM of 158 ± 17 nm. The VO₂ sample (grown under identical conditions to that in the multilayers) also gave a thickness of 70 nm. This thickness discrepancy relates to the use of the bulk densities of the components in the modelling. The density is inversely proportional to the layer thickness. It is very likely that the density of the VO₂ under the TiO₂ is lower than the VO₂ deposited on top of TiO₂ and that of the bulk value when considering that it will be in the same porous form as the reference VO₂ sample, as seen in the SEM morphologies.

3.6. X-ray photoelectron spectroscopy

No samples showed any sign of any impurities, except for carbon, which was to be expected. Both multilayer samples established that only the top layer could be detected by XPS, confirming the formation of coherent films with no pin-holes or diffusion to the surface of other chemical species. Confirmation of this can be seen in Fig. 7 where the high resolution scans for Ti 2p and V 2p are shown for both samples.

For the TiO₂ over VO₂ sample, the Ti 2p spectrum showed the expected 2p_{1/2} and 2p_{3/2} features at 465.05 and 459.28 eV, respectively, which relate to Ti⁴⁺ attached to O²⁻ [20], with a splitting of 5.77 eV. There was no shift in position from that of the reference TiO₂ sample. Again the width of the peaks at 0.80 eV is in line with that seen for the reference (0.86 eV) and is indicative of TiO₂ with low structural disorder [21]. High resolution O 1s spectra confirm the presence of TiO₂ (530.05 eV), along with

a low intensity signal at 531.82 eV relating to absorbed water [22].

The V 2p spectrum, for the VO₂ over TiO₂ sample, is similar to that of the reference VO₂ sample in both position (2p_{3/2} at approximately 516.4 eV, with a splitting of 7.68 eV) and width. This is the position for a vanadium oxide (515.5–517.5 eV) [23], but accurate assignment of this feature is complicated by spectral asymmetry broadening towards higher B.E., which could be misinterpreted as a shoulder for the next oxidation state. Due to this it is more usual to discuss the average oxidation state via the positions of the raw data relative to the O 1s signal [24].

$$V_{\text{ox}} = 13.82 - 0.68(\text{O } 1s - \text{V } 2p_{3/2})$$

These calculations led to identical average oxidation states for the reference VO₂ and that of the multilayer of 4.7. Looking closely at the V 2p spectrum it is possible to resolve this into 2 species of average oxidation state 4.4 and 5.2. The multilayer and VO₂ reference samples being approximately 49 and 35% average oxidation state 4.4, respectively. However, it is important to bear in mind that these figures do not necessarily reflect the structure of the bulk or as grown sample. In comparison the bulk stoichiometry was confirmed by RBS, which also agrees with the XRD result for TiO₂ over VO₂.

Another issue with XPS of vanadium is the tendency of the lower oxidation states to oxidise to V⁵⁺ (most stable state V₂O₅) when exposed to ambient conditions. As XPS is a surface sensitive technique sampling a depth of approximately 5 nm it is this state that is most readily detected. In theory etching the top surface via an Ar⁺ ion beam should help, but in practice this leads to the reduction of the V species [25]. All this makes it difficult to extract full details of exact chemical species present.

3.7. UV/visible spectroscopy

The absorbance of the thermally grown TiO₂ reference gave a sharp peak at 318 nm, while that of the VO₂ had a much broader

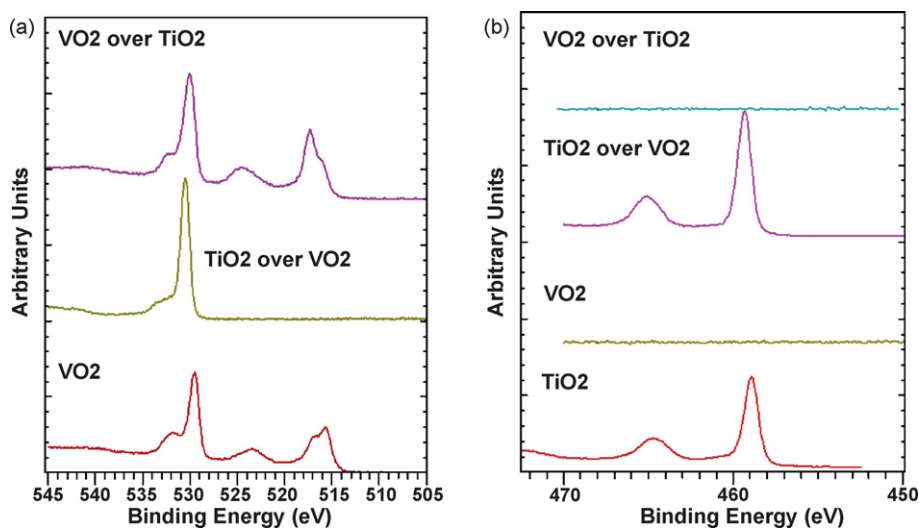


Fig. 7. XPS of (a) O 1s and V 2p and (b) Ti 2p.

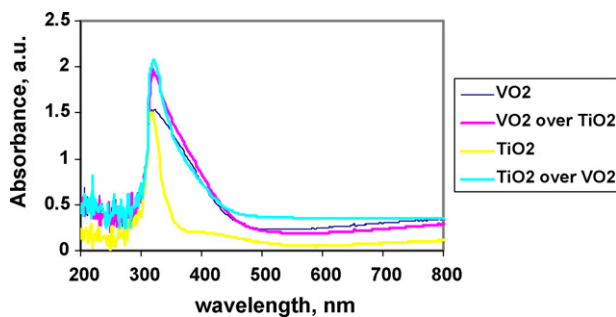


Fig. 8. UV/visible absorbance spectra.

signal to lower energy, Fig. 8. This was to be expected due to the colouration of the VO₂.

The appearance of a peak, rather than an edge, is due to removal of the background from the glass substrate (so only the effects of the deposited film were seen) and the uncorrected spectral response of the spectrometer. As can be seen in Fig. 8, the multilayer samples gave basically an amalgamation of these signals, although with a small shift of the TiO₂ band edge to 322 nm.

3.8. Contact angle

Results shown, in Table 1, are the average of 5 angle measurements for before and after 60 min of 365 nm, 3 mW cm⁻² UV radiation. These are for samples at room temperature. All samples showed a reduction in the contact angle after UV radiation, showing an increased hydrophilicity.

That of the VO₂ with an over-layer of TiO₂ showed the greatest overall change, along with the lowest angle after radiation. The after radiation value is comparable with the reference TiO₂ sample, although the pre-radiation value is higher showing a slightly increased hydrophobic nature. Overall there was no adverse change in the hydrophilicity by growth on VO₂ rather than directly on glass. Although the two samples of VO₂ (direct on glass or via a layer of TiO₂) have very different morphologies (as seen by the SEM) the actual changes and values of the contact angle are very similar.

3.9. Thermochromic properties

To assess the thermochromic behaviour of the samples the reflection and transmission were measured at a range of temperatures. Care was taken (using a hand held temperature probe) to assure that the sample surface had reached the required temperature and not just the heating stage. A 5 °C difference in

Table 1
Contact angle results

| Sample | Before UV radiation (°) | After UV radiation (°) |
|---------------------------------------|-------------------------|------------------------|
| TiO ₂ over VO ₂ | 63.70 ± 2.85 | 18.45 ± 2.23 |
| VO ₂ over TiO ₂ | 54.30 ± 0.77 | 40.91 ± 7.98 |
| VO ₂ | 54.50 ± 2.54 | 32.30 ± 2.50 |
| TiO ₂ | 56.51 ± 1.46 | 18.00 ± 0.88 |

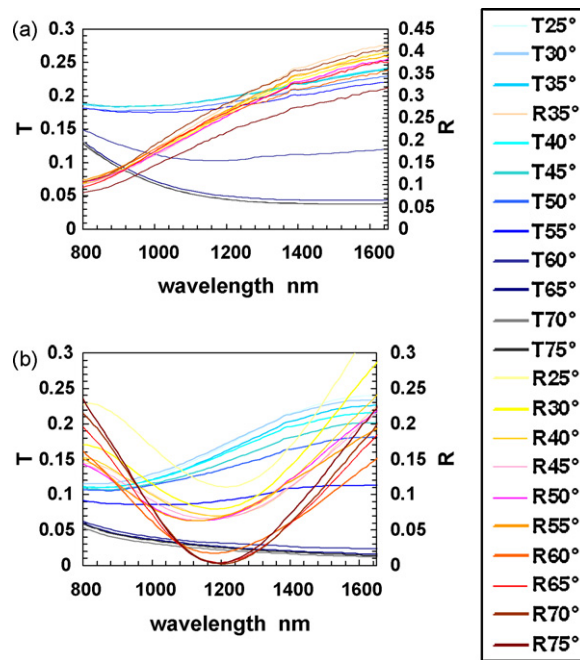


Fig. 9. Reflection and transmission spectra changes with temperature (a) VO₂ and (b) TiO₂ over VO₂.

stage temperature and sample temperature was observed. All measurements shown give the temperature of the sample.

The reflection and transmission spectra shown in Fig. 9(a) show a relatively simple structure for the reference VO₂. The transmission spectra have a blue tone and the reflection have a red or yellow tone legend.

A clear change, particularly in the transmission curve can be seen to be occurring from 55 to 65 °C. These spectra become more complex as TiO₂ is added to the structure. For example Fig. 9(b) shows the spectra for TiO₂ over VO₂. There is now more structure particularly to the reflectance curves. Again the transition between the monoclinic and tetragonal VO₂ structure reflected in the optical change can be seen between 50 and 60 °C.

To more accurately pin-point the temperature at which the change occurs, values of reflectance and transmission were extracted at 1500 nm and plotted against temperature. Although both the reflection and transmission changes can be seen (Fig. 10), the change in the transmission is particularly apparent.

The sample of TiO₂ over VO₂ had a lower temperature switching point than that of the VO₂ reference, which was marginally better than that of the VO₂ over TiO₂ structure. For a more quantitative analysis of the thermochromic effect, temperatures were chosen at which complete change would have occurred, i.e. 25 and 65 °C. From these values the percentage change in available light was calculated as shown below. The results are shown in Table 2.

$$\frac{T_{25} - T_{65}}{T_{25}} \times 100 = \% \text{change};$$

$$\frac{R_{25} - R_{65}}{R_{25}} \times 100 = \% \text{change}$$

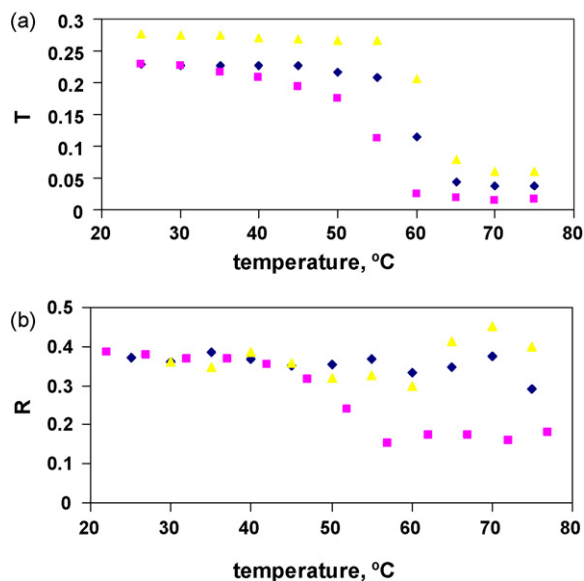


Fig. 10. Optical data at 1500 nm. (a) Transmission measurements VO₂ over TiO₂ ▲, TiO₂ over VO₂ ■, VO₂ over TiO₂ ◆. (b) Reflection measurements.

For all three samples, there was a decisive reduction in transmission over the VO₂ transition temperature. However, the reflectance change was not as clearly marked, being over a smaller range of values, with a comparatively higher degree of scatter.

A greater change in reflectance was shown for the multilayer samples than that of the individual VO₂ sample. Interestingly, the VO₂ sample with an over-layer of TiO₂ showed a decrease in reflectance at the transition temperature, while that of the TiO₂ sample capped with VO₂ showed an increase. This observation may be understood by considering the interaction of the relative refractive indices in the multilayers, and especially the change in refractive index of the VO₂ upon transition from the monoclinic to the tetragonal crystal system (the precise value for particularly VO₂ depending on growth conditions. VO₂ monoclinic; $n=2.8\text{--}3.20$ [26,27], VO₂ tetragonal; $n=1.1\text{--}1.6$ [26], TiO₂ anatase; $n=2.5$, air; $n=1$). The basic concept of relevance is that used in simple colour suppression layers, where via a judicious matching of refractive indices present in multilayer systems interference effects can be used to tailor the appearance of a film, over selected wavelength regions [28]. When a wave is reflected from the surface of a material of higher refractive index it ideally undergoes a 180° phase change, but when the material has a lower refractive index there is no phase change. In the case of the TiO₂ over monoclinic VO₂ there is an increase in refractive index at each subsequent sur-

face (air < TiO₂, TiO₂ < VO₂), hence the light reflected at the air/TiO₂ interface undergoes a 180° phase reversal, and the light reflected on the TiO₂/monoclinic VO₂ interface also undergoes a 180° phase, these waves therefore emerge constructively. When the sample is heated above the transition temperature, the VO₂ becomes tetragonal and has a lower refractive index than that of the TiO₂, the light involved in the second reflection (i.e. on the VO₂ surface) does not undergo a phase change, therefore the light reflected from the two interfaces emerges destructively. This is in agreement with our observations, the reflectance of the TiO₂ over VO₂ sample decreased above the transition temperature.

In the case of VO₂ over TiO₂, below the transition temperature (i.e. in the monoclinic form), there is a phase change at the air/VO₂ interface (air < VO₂ monoclinic) but no phase change at the VO₂/TiO₂ interface (VO₂ monoclinic > TiO₂), these waves therefore emerge destructively. Above the transition temperature the tetragonal VO₂ has a refractive index lower than TiO₂, therefore a phase change occurs at both interfaces, and these waves emerge constructively. This is also in agreement with our observations, the reflectance of the VO₂ over the TiO₂ sample increased above the transition temperature.

The phase shift upon reflection depends also on the relationship between wavelength and layer thickness. In the specific case where the layer thickness = $\lambda/(4n)$ then complete destructive interference will arise. However, this is a very specific case and for this reason does not generally apply. Thus, overall, at any given wavelength there will be a contribution towards loss of intensity as a result of interference, but by far the most significant effects will arise from a consideration of relative refractive indices.

Within the literature no exact comparison could be found in terms of switching temperatures, due to the fact that the multilayer systems described here have not been made previously. All samples containing VO₂ (multilayers and reference), switched between 50 and 60 °C—temperatures which are comparable to those reported previously with values ranging from 70 °C [29], through 68 °C [19,30,31] to 53 °C [18]. The higher switching temperatures relate to VO₂ only, while the lower values relate to a film containing a mixture of mainly VO₂ doped with some TiO₂ [18]. In this work, the reduction in switching temperature was considered to be due to the effects of strain induced by the TiO₂ within the VO₂. The presence of strain within the VO₂ layer would help explain the reduced switching temperature for the TiO₂ over VO₂ sample studied here as compared to the VO₂ reference. However, little difference was seen in the VO₂ over TiO₂ sample despite the presumed presence of strain. From other studies on the effect of strain on the switching temperature the orientation of the underlying layer is of importance, leading to increases or decreases in transition temperature [32]. Therefore, the change produced is a product of the various strains the growing layer is under. In our case, we noted earlier that for the VO₂ over TiO₂ sample, the morphology of the VO₂ film was essentially that of the underlying TiO₂ film, which appears to act as a template for growth. Thus, it is possible that morphology, possibly grain size, is the dominant factor here, rather than strain itself.

Table 2
Percentage transmission and reflectance changes

| Sample | Transmission change (%) | Reflectance change (%) |
|---------------------------------------|-------------------------|------------------------|
| VO ₂ | 81 | 6 |
| TiO ₂ over VO ₂ | 92 | 55 |
| VO ₂ over TiO ₂ | 71 | −55 |

Table 3

Data for solar calculations above and below the transition temperature for VO₂ containing samples

| Sample | %Transmittance | |
|---------------------------------------|----------------|-------|
| | 25 °C | 65 °C |
| TiO ₂ over VO ₂ | 12.9 | 4.9 |
| VO ₂ | 18.8 | 10.9 |
| VO ₂ over TiO ₂ | 22.9 | 14.6 |

From this data solar transmittance can be calculated according to a standard solar energy distribution curve defined by the ASTM which represents average solar irradiation at sea level in the middle of the northern hemisphere. This assumes a tilt of 37°, which is the average angle of the sun's rays impinging off a vertical surface (in the Northern hemisphere). This was calculated for the samples both above (65 °C) and below (25 °C) the VO₂ transition temperature. The data is shown in Table 3.

It was shown that the percentage transmittance (in IR) fell, as would be expected, after the VO₂ transition to the tetragonal rutile form. That for TiO₂ over VO₂ showed the greatest change and the lowest IR (i.e. heat) transmittance after the VO₂ transition temperature. For a glazing application this reduced IR transmittance after the transition temperature would be an advantage. Indeed, for some potential application areas (e.g. automotive roof-lights) low transmission levels are desired.

3.10. Photocatalytic behaviour

This was determined by the decomposition of stearic acid under both UV and visible light. It can be seen in Fig. 11 that as expected the TiO₂ reference is highly photoactive, while the VO₂ reference is not (0.0004 cm⁻¹ min⁻¹). From tests using standard float glass a gradient of $\leq 10^{-4}$ cm⁻¹ min⁻¹ is assumed to represent an inactive sample. The sample of TiO₂ over VO₂ is also photoactive (0.0057 cm⁻¹ min⁻¹) comparing favourably to the activity of the reference (0.0046 cm⁻¹ min⁻¹).

No literature data was found for multilayers comparable to those described here, but for sol-gel mixtures of TiO₂ with vanadium in different oxidation states (V⁵⁺ [33,34], V⁴⁺ [35,36])

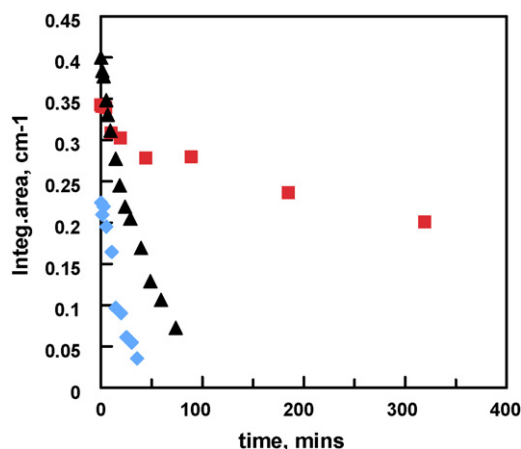


Fig. 11. UV photoactivity for TiO₂ on VO₂ ◆, VO₂ ■ and TiO₂ ▲.

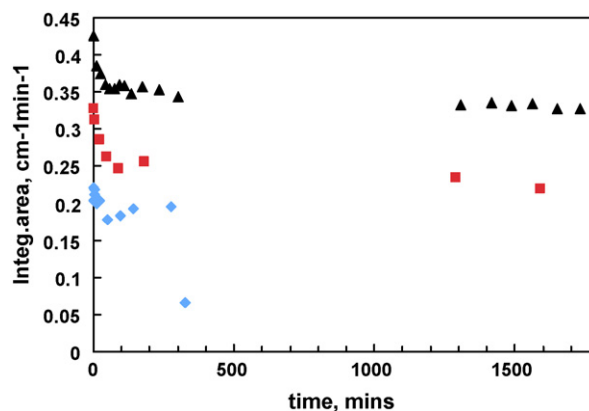


Fig. 12. Visible activity of TiO₂ on VO₂ ◆ and references VO₂ ■ and TiO₂ ▲.

addition of V ions was considered to improve the photoactivity of the materials. However, too great a doping level of V in TiO₂ was expected to reduce photoactivity activity [37]. Only one research group has used CVD to produce mixed films of TiO₂ and VO₂, rather than the discrete multilayers described here. The authors [38] suggested that the VO₂ films exhibited proportional photoactivity to the titania present in the layer, although no values were given.

From Fig. 12 it can be seen that no visible activity was seen (or expected) for VO₂ or TiO₂ (10⁻⁵ cm⁻¹ min⁻¹). In the literature there are some claims for visible activity of V-doped TiO₂. Earlier work [39] reported that doping TiO₂ with V shifted the bandgap toward the visible part of the spectrum and in some cases reported photoactivity in the visible [40,41]. However, in spite of the band edge shift towards longer wavelength for our multilayered samples the measured rate of reaction was 10⁻⁴ cm⁻¹ min⁻¹ and thus no visible activity was observed.

This lack of visible activity could be due to the lack of interaction between layers, as established by XPS with no detectable doping caused by ion migration. However, previous reports in the literature for doped TiO₂-V gave a very mixed opinion as to the existence or otherwise of true visible light photoactivity while the lack of visible activity and reduced UV activity observed in our experiments was in good agreement with the findings of many other groups [42,43]. Also, we note that in some cases where visible light induced photoactivity had been claimed, the experimental methodologies employed have been questionable- for example via the failure to adequately filter out uv light during the measurements [41].

3.11. Durability

All films adhered strongly to the substrate (as determined by the adhesive-tape peel test). Bulk vanadium oxides are amphoteric, dissolving in both acids and alkalis [44]. So to assess the degree to which the TiO₂ layer could act as a protective (as well as self-cleaning) coating towards the underlying VO₂, samples of VO₂ and TiO₂ over-coated VO₂ were placed in a 2 M NaOH aqueous solution for 4 h. The relatively aggressive conditions (compared to potential “in use” exposure) were specifically chosen to show the dramatic protective effect provided by the

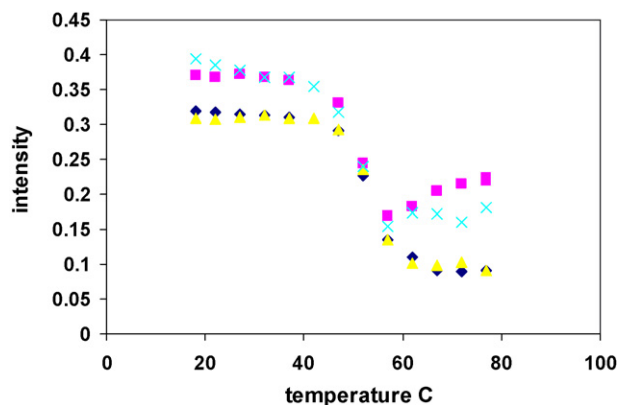


Fig. 13. Spectrophotometry data for comparison of TiO₂ over VO₂ before and after NaOH etch. Reflection before x and after ■, transmission before ▲ and after ◆.

TiO₂ layer. The edges of the samples were masked using PVC adhesive-tape to prevent ‘peeling’ of the TiO₂ over-layer via dissolution of the VO₂ underlayer as a result of contact with the alkali at the exposed edges.

After 4 h the VO₂ had completely dissolved in the exposed area, this was expected and was in line with previously reported work [25]. Upon removal of the tape around the edges, the coating remained intact and clearly visible, showing good adhesion to the substrate. The exposed TiO₂ surface remained unchanged, showing no visible signs of degradation or dissolution to eye or optical microscope. Upon removal of the PVC tape the coating remained intact, indicating good inter-layer and substrate adhesion. Subsequent XRD of the sample showed the structure of both the TiO₂ and the VO₂ were unchanged, and XPS analysis only detected peaks corresponding to TiO₂ with no vanadium detected, confirming that the surface was still intact with no pin-holes.

The sample was re-tested for its photocatalytic activity, the sample remained highly photoactive (0.0040 cm⁻¹ min⁻¹), showing only a small decrease compared to its photoactivity (0.0057 cm⁻¹ min⁻¹) before the durability test. Such a small decrease in photoactivity after exposure to such aggressive testing again highlights the resilience of TiO₂ as a protective layer.

As a final test to confirm the durability of this sample the thermochromic behaviour of the VO₂ underlayer was again tested (after the NaOH etch). There was no change in the switching temperature or in the absolute transmission and reflection of the sample, beyond that of instrumental and experimental error variation, as can be seen in Fig. 13.

4. Conclusions

APCVD has been used to deposit thin films of VO₂, TiO₂ and their combinations. All materials were shown to be polycrystalline, consisting of anatase for the TiO₂ layers, and either monoclinic VO₂ or mixed vanadium oxides. All samples containing vanadium oxide species showed thermochromic properties with the lowest switching temperature recorded being 55 °C for a sample of VO₂ with an over-layer of TiO₂. This temperature was lower than that of the reference VO₂ sample due

to the strain within the system. Photocatalytic behaviour, in the UV, with the degradation of stearic acid for TiO₂ over VO₂ was comparable to that of the reference TiO₂ sample.

With a multilayer of TiO₂ over VO₂ we have produced layers, which show the combined functionality of photoactivity with that of thermochromicity. The resulting dual layer system displays enhanced resistance to chemical attack as compared to the reference VO₂ film alone.

This work has demonstrated for the first time, the efficacy of the APCVD approach for the fabrication of films, which show dual functionality in the form of protection/self-cleaning and thermochromicity. It is anticipated that this approach could offer commercial potential in the production of glazing units designed to reduce building and vehicle energy costs while requiring minimal routine maintenance. In particular, the enhanced durability offers potential for monolithic (i.e. single pane) glazing which can have major cost benefits and is an attractive option in certain climates. As such these dual layer systems represent a potentially major step forward in the development of smart glazing materials.

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